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(71) Applicant: **MERCK PATENT GMBH** [DE/DE]; Frank-
furter Straße 250, 64293 Darmstadt (DE).

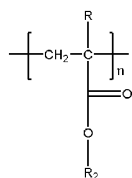
(72) Inventors: **DAMMEL, Ralph R.**; c/o EMD Performance
Materials Corp., 70 Meister Avenue, Branchburg, New Jer-
sey 08876 (US). **BUHBUT, Sophia**; c/o EMD Performance
Materials Corp., 70 Meister Avenue, Branchburg, New Jer-

sey 08876 (US). **IRZH, Alex**; c/o EMD Performance Ma-
terials Corp., 70 Meister Avenue, Branchburg, New Jer-
sey 08876 (US). **KOOLYK SHARABI, Miriam**; c/o EMD
Performance Materials Corp., 70 Meister Avenue, Branch-
burg, New Jersey 08876 (US). **NOLL, Sina**; c/o EMD Per-
formance Materials Corp., 70 Meister Avenue, Branchburg,
New Jersey 08876 (US). **NEYSHTADT, Shany**; c/o EMD
Performance Materials Corp., 70 Meister Avenue, Branch-
burg, New Jersey 08876 (US).

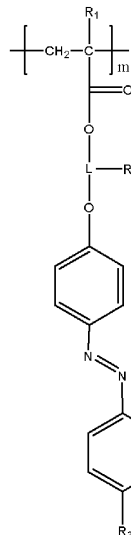
(74) Agent: **SCHUCK, Alexander**; Patentanwälte Isenbruck
Bösl Hörschler PartG mbB, Seckenheimer Landstraße 4,
68163 Mannheim (DE).

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(54) Title: DSA OF LIQUID CRYSTAL BLOCK COPOLYMERS FOR INTEGRATED CIRCUIT PATTERNING



(I)



(II)

(57) Abstract: Described is a block copolymer, which is an AB diblock copolymer with a first block A of structure (I) and a second block B of structure (II), wherein R and R₁ are individually selected from a C-1 to C-4 alkyl, where the mole % of repeat units of structure (I) ranges from about 35 mole % to about 94 mole %, and the mole % of repeat units of structure (II) ranges from about 6 mole % to about 65 mole %, R₂ is selected from a C-1 to C-11 alkyl, L is a C-5 to C-12 linear alkylene, and R₃ is selected from a C-3 to C-8 linear alkyl, R' is H or a C-3 to C-8 linear alkyl wherein said block copolymer has a poly dispersity of 1 to about 1.31. Also described are compositions of this block copolymer in a solvent and their use in DSA processing.

[Continued on next page]

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